

	Type	L #	Hits	Search Text	DBs	Time Stamp	Com men ts	Er ro r D ef in iti on	Er ro rs
1	BRS	L8	55	((TREAT\$3 OR EXPOS\$3 OR FORM\$3 OR APPL\$4) WITH PLASMA) SAME ("NON OXIDE" OR "NON OXIDE CERAMIC" OR "MACHINED OR SINTERED")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/23 15:51			0
2	BRS	L15	26	8 AND @PD<=19990620	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/23 15:58			0
3	BRS	L22	3086	((TREAT\$3 OR EXPOS\$3 OR FORM\$3 OR APPL\$4) WITH PLASMA) SAME (SiC OR "SILICON CARBIDE" OR GRAPHITE )	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/23 16:03			0
4	BRS	L29	1667	((TREAT\$3 OR EXPOS\$3 OR FORM\$3 OR APPL\$4) WITH PLASMA) with (SiC OR "SILICON CARBIDE" OR GRAPHITE )	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/23 15:58			0
5	BRS	L36	1229	29 AND @PD<=19990620	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/23 15:59			0
6	BRS	L43	0	"38" and "438"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/23 15:59			0
7	BRS	L50	124	36 and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/23 15:59			0

	Type	L #	Hits	Search Text	DBs	Time Stamp	C o m m e n t s	E r r o r s
8	BRS	L57	0	(TREAT\$3 OR EXPOS\$3 OR APPL\$4) WITH (PLASMA near5 high\$3 near5 (intensity or density)) with ((sinter\$3 or machin\$3) adj3 (SiC OR "SILICON CARBIDE" OR GRAPHITE or carbon or Si or silicon or "silicon nitride" or "boron nitride" or BN or SiN or Si3N4 or AlN or "aluminum nitride" or "titanium carbide" or TiC))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/23 16:22		0
9	BRS	L64	10	((TREAT\$3 OR EXPOS\$3 OR APPL\$4) WITH (PLASMA near5 high\$3 near5 (intensity or density))) and ((sinter\$3 or machin\$3) adj3 (SiC OR "SILICON CARBIDE" OR GRAPHITE or carbon or Si or silicon or "silicon nitride" or "boron nitride" or BN or SiN or Si3N4 or AlN or "aluminum nitride" or "titanium carbide" or TiC))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/23 16:26		0